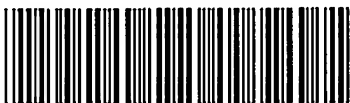


Search Notes

Application No.

10/603,976

Examiner

Stephen W. Smoot

Applicant(s)

JUNG ET AL.

Art Unit

2813

SEARCHED

Class	Subclass	Date	Examiner
438	637	7/19/2004	SWS
438	675	7/19/2004	SWS
438	684	7/19/2004	SWS
438	692	7/19/2004	SWS
438	693	7/19/2004	SWS
252	79.1	7/19/2004	SWS
252	79.2	7/19/2004	SWS
Updated	Above	12/22/2004	SWS
51	307	12/22/2004	SWS

INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: CMP - Chemical Mechanical Polishing, Perchloric Acid, Chloric Acid, Hypochlorous Acid,	7/19/2004	S.W.S., SWS
Bromic Acid, Perbromic Acid, Iodic Acid, Periodic Acid, Hard Pad;	7/19/2004	S.W.S., SWS
Wordline - Polysilicon, Nitride Mask, Spacer, Contact Hole, Interlayer - BPSG, FSG, USG, PSG, TEOS.	7/19/2004	S.W.S., SWS
Updated Above Search	12/22/2004	S.W.S., SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	7/19/2004 & 12-22-04	SWS S.W.S.